**ESI 3511 Downstream Plasma Asher**

The control interface might be logged out (most menus are grey-unavailable). If so, click on “Log In” top of screen and select “EPFL_Users”. Password is “1”.

Chamber might be at “HIBERNATE” state. If so, no recipe can be started. Click on “Stop Hibernate” and wait for the chamber to return at atmospheric pressure.
The chamber is now “READY” and the button “Select Rcp” is available.

Click on “Select Rcp”, make you selection according to your needs, and confirm “Yes”.

The chamber now reads “SET_UP”. It is stabilizing the temperature to reach recipe setpoint. When the chamber is OK for process it reads “READY”.

[Diagram of chamber interface with buttons and settings]
Load your wafers in the cassette. **Please mind the position of your wafers:**

- Make sure the wafers are loaded horizontal!!
- Remember about slots number your wafers are loaded into.

Click “Run” button, input your **lot ID** (optional), and click **OK**.
Select the wafers **“ON”** according to where the wafers are physically loaded in the cassette and confirm **OK**. Confirm **“OK”** to start the run.
The “Robot-1” Status will change from “IDLE” to “TRANSFER”.

Through the process, live value of each parameters can be visualized by using the button “Graphs”. This include optical end-point detection.

At end of the process, the summary of processed wafers appears.

![Wafer Selection](image)

Collect the wafers, place the cassette back to correct position, and “Start Hibernate” the chamber.